

PATENT ABSTRACTS OF JAPAN

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(71)Applicant : **CANON INC**

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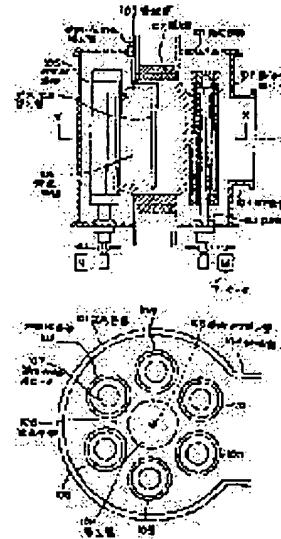
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(54) MICROWAVE PLASMA CVD APPARATUS

(57)Abstract:

PURPOSE: To offer an apparatus for forming a deposited film capable of stably forming a functional deposited film having good properties at low cost in high yield at high speed by a microwave plasma CVD method.

CONSTITUTION: As for a microwave introducing window 102, alumina is used as a base metal, to which partially stabilized zirconia is added in the range of 1 to 90% and is uniformly dispersed, and baking is executed into an alumina-zirconia base composite. In this way, its durability to severe use by the repetition of the formation of a film on a microwave introducing window by a microwave plasma CVD method and the removal of the deposited film as posttreatment after the film forming can be improved.



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